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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO. CONFIRMATION NO.	
10/624,185	07/22/2003	Philip James Rae	020569-00700	6857
7:	90 07/01/2005		EXAM	INER
John Wilson Jones Attn: IP Docketing Clerk			WALKER, ZAKIYA NICOLE	
Locke, Liddell & Sapp LLP			ART UNIT	PAPER NUMBER
600 Travis, Suite 3400 Houston, TX 77002			3676	

DATE MAILED: 07/01/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)			
	10/624,185	RAE ET AL.			
Office Action Summary	Examiner	Art Unit			
	Zakiya N. Walker	3676			
The MAILING DATE of this communication ap	.1 -				
Period for Reply A SHORTENED STATUTORY PERIOD FOR REPL THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1. after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a rep - If NO period for reply is specified above, the maximum statutory period - Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailin	136(a). In no event, however, may a reply be tir ly within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from e, cause the application to become ABANDONE	nely filed rs will be considered timely. the mailing date of this communication. ED (35 U.S.C. § 133).			
earned patent term adjustment. See 37 CFR 1.704(b). Status					
_					
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims					
4) ⊠ Claim(s) <u>1-29</u> is/are pending in the application 4a) Of the above claim(s) is/are withdra 5) □ Claim(s) is/are allowed. 6) ⊠ Claim(s) <u>1-4,6-8,10-12,16,17,20-26,28 and 29</u> 7) ⊠ Claim(s) <u>5,9,13-15,18,19 and 27</u> is/are objects 8) □ Claim(s) are subject to restriction and/o	wn from consideration. g is/are rejected. ed to.				
Application Papers					
9) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) acc Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the E	cepted or b) objected to by the drawing(s) be held in abeyance. Se tion is required if the drawing(s) is ob	e 37 CFR 1.85(a). sjected to. See 37 CFR 1.121(d).			
Priority under 35 U.S.C. § 119					
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No. 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 					
Attachment(s)					
1) Notice of References Cited (PTO-892) 4) Interview Summary (PTO-413) Paper No(s)/Mail Date					
 Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date <u>07222003,11122004</u>. 		Patent Application (PTO-152)			

Application/Control Number: 10/624,185

Art Unit: 3676

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 2. Claims 1-4, 8, 10, 12, 16, 17, and 20-26 are rejected under 35 U.S.C. 102(e) as being anticipated by Shuchart et al. (cited by applicant).

Shuchart et al. discloses a method that includes a process for dissolving acidsoluble siliceous material in a sandstone formation of an oil or gas well that comprises:

(a) introducing into the well a buffered acid solution containing an organic
acid (citric), the buffered acid solution being void of hydrofluoric acid or a hydrofluoric
acid precursor; and (b) introducing into the well an HF-containing sandstone acidizing
solution wherein the pH of the buffered acid solution has pH substantially equivalent to
that of the acidizing solution. With respect to depending claims 2-4, 8, 10, and 12, the
reference teaches the limitations as claimed, including the buffered solution contains
HCL (pre-flush and overflush), buffered solution does not contain inorganic acids, and
the buffered solution comprises organic acid and salt. With respect to claim 16, the
reference discloses a process for dissolving acid soluble siliceous material in a well

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which comprises: (a) introducing into the well a HF containing acidizing solution having a pH of between from about 1.9 to about 4.5; and (b) prior to and/or subsequent to step (a) introducing into the well a buffered acid solution, void of hydrofluoric acid, having a pH of from about 1.9 to about 4.5. With respect to depending claim 17, the reference teaches the two solutions having a substantially equivalent pH. With respect to claim 20, the reference discloses a process for removing carbonate materials or scale deposition from a subterranean formation of an oil or gas well which comprises introducing into the well a buffered acid solution containing an organic acid and void of hydrofluoric acid or a hydrofluoric acid precursor wherein the pH of the buffered acid solution is generally between from about 1.9 to about 4.8. With respect to depending claims 21-26, the reference e teaches the limitations as claimed including a sandstone formation, a carbonate formation, the buffered solution contains HCL (pre-flush and overflush), buffered solution does not contain inorganic acids, and the buffered solution comprises organic acid and salt.

3. Claims 1-4, 6-8, 10-12, 16, 17, 20-26, 28, and 29 are rejected under 35 U.S.C. 102(b) as being anticipated by Lybarger et al.

Lybarger et al. discloses a method that includes a process for dissolving acid-soluble siliceous material in a sandstone formation of an oil or gas well that comprises:

(a) introducing into the well a buffered acid solution containing an organic acid (formic), the buffered acid solution being void of hydrofluoric acid or a hydrofluoric acid precursor; and (b) introducing into the well an HF-containing sandstone acidizing solution (slug 9) wherein the pH of the buffered acid solution has pH substantially

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equivalent to that of the acidizing solution. With respect to depending claims 2-4, 6-8, and 10-12, the reference teaches the limitations as claimed, including the buffered solution contains HCL, buffered solution does not contain inorganic acids, the buffered solution consists essentially of/comprises organic acid and salt (slug 11), and the organic salt is an ammonium salt of acid. With respect to claim 16, the reference discloses a process for dissolving acid soluble siliceous material in a well which comprises: (a) introducing into the well a HF containing acidizing solution having a pH of between from about 1.9 to about 4.5; and (b) prior to and/or subsequent to step (a) introducing into the well a buffered acid solution, void of hydrofluoric acid, having a pH of from about 1.9 to about 4.5. With respect to depending claim 17, the reference teaches the two solutions having a substantially equivalent pH. With respect to claim 20, the reference discloses a process for removing carbonate materials or scale deposition from a subterranean formation of an oil or gas well which comprises introducing into the well a buffered acid solution containing an organic acid and void of hydrofluoric acid or a hydrofluoric acid precursor wherein the pH of the buffered acid solution is generally between from about 1.9 to about 4.8. With respect to depending claims 21-26, the reference teaches the limitations as claimed including a sandstone formation, a carbonate formation, the buffered solution contains HCL, buffered solution does not contain inorganic acids, the buffered solution comprises organic acid and salt, and the organic salt is an ammonium salt of acid.

Allowable Subject Matter

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4. Claims 5, 9, 13-15, 18, 19, and 27 are objected to as being dependent upon a

rejected base claim, but would be allowable if rewritten in independent form including all

of the limitations of the base claim and any intervening claims.

Conclusion

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Zakiya N. Walker whose telephone number is (571) 272-

7039. The examiner can normally be reached on Monday-Friday, 8:30 AM-5 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Brian Glessner can be reached on (571) 272-6843. The fax phone number

for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the

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you have questions on access to the Private PAIR system, contact the Electronic

Business Center (EBC) at 866-217-9197 (toll-free).

Zakiya N. Walker

Primary Examiner

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June 20, 2005